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L1: Entry 1 of 2

File: EPAB

May 30, 1984

PUB-N0: DE003240643A1

DOCUMENT-IDENTIFIER: DE 3240643 A1

TITLE: Production of conductor track coatings and conductive hole wall coatings on or in circuit boards

PUBN-DATE: May 30, 1984

INVENTOR-INFORMATION:

NAME	COUNTRY
TOLLS, ELMAR DR	DE
SCHNEIDER, EHRENHARD	DE
PLATZEN, ROLF	DE

ASSIGNEE-INFORMATION:

NAME	COUNTRY
LPW CHEMIE GMBH	DE

APPL-NO: DE03240643

APPL-DATE: November 4, 1982

PRIORITY-DATA: DE03240643A (November 4, 1982)

US-CL-CURRENT: 205/164; 205/920

INT-CL (IPC): C25D 7/00; C25D 3/38

EUR-CL (EPC): C25D003/38

ABSTRACT:

CHG DATE=19990617 STATUS=> A copper bath, known in connection with the production of bright copper precipitates, of the composition 10-50 g/l of copper as +2-valent ions, 20-220 g/l of sulphuric acid and 1-200 mg/l of chloric acid is used for the electrolytic production of circuit board coatings and conductive hole wall coatings in circuit boards having holes. The copper bath additionally contains polyglycol and/or nonionic wetting agents and organic thio compounds having water-solubilising groups, but is free of planarisers. This is carried out at a temperature of more than 30 DEG C, preferably about 40 DEG C, and the current density is maintained in the range 5-15 A/dm².

WEST**End of Result Set**

L1: Entry 2 of 2

File: DWPI

May 30, 1984

DERWENT-ACC-NO: 1984-140962

DERWENT-WEEK: 198423

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TITLE: Copper electroplating printed circuit board contg. through-holes - from bath contg. added polyglycol or nonionic wetting agent and organic thio cpd. operated at high temp. and current density

INVENTOR: PLATZE, R; SCHNEIDER, E ; TOLLS, E

PATENT-ASSIGNEE:

ASSIGNEE	CODE
LPW-CHEMIE GMBH	LPWCN

PRIORITY-DATA: 1982DE-3240643 (November 4, 1982)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
<u>DE 3240643 A</u>	May 30, 1984		008	
<u>DE 3240643 C</u>	January 21, 1988		000	

APPLICATION-DATA:

PUB-NO	APPL-DATE	APPL-NO	DESCRIPTOR
DE 3240643A	November 4, 1982	1982DE-3240643	

INT-CL (IPC): C25D 3/38; C25D 7/00

ABSTRACTED-PUB-NO: DE 3240643A

BASIC-ABSTRACT:

In using a standard bright Cu plating bath contg. 10-50 g/l cupric ions, 20-200 g/l H₂SO₄ and 1-200 mg/l chloride ions for electroplating printed circuit boards contg. through-holes, the plating bath additionally comprises polyglycol or nonionic wetting agents and organic thio-cpds. contg. water-solubilising gps. but is free from levelling agents. Plating takes place above 30(40) deg.C and current density is kept at 5-15 A/sq.dm.

On increasing the temp. and average current density, plating time is reduced, e.g. to 20 min. for applying a 30 mu-thick layer. A good layer thickness distribution of hole wall to surface is achieved. The Cu layer has high ductility.

ABSTRACTED-PUB-NO:

DE 3240643C

EQUIVALENT-ABSTRACTS:

In the prodn. of conductor plates drilled with holes a smooth copper coating of the plates is achieved by using a copper bath free from levels and contg. 10-50 g/l Cu as divalent ions, 20-220 g/l sulphuric acid, 1-220 mg/l chloride ions, polyglycol or nonionic wetting agents and organic thio cpds. with gps. making them water soluble and working at temps. over 30(40) deg.C and with current density 5-15 A/dm².

ADVANTAGE - Copper is deposited smoothly and layer has high ductility.

(3pp)

CHOSEN-DRAWING: Dwg.0/0

TITLE-TERMS: COPPER ELECTROPLATING PRINT CIRCUIT BOARD CONTAIN THROUGH HOLE BATH
CONTAIN ADD POLYGLYCOL NONIONIC WET AGENT ORGANIC THIO COMPOUND OPERATE HIGH
TEMPERATURE CURRENT DENSITY

DERWENT-CLASS: A97 L03 M11 V04

CPI-CODES: A05-H01; A12-E07A; A12-W12D; L03-H04E3; M11-A03;

EPI-CODES: V04-R02; V04-R05;

UNLINKED-DERWENT-REGISTRY-NUMBERS: 1714S; 1759S ; 5214U

POLYMER-MULTIPUNCH-CODES-AND-KEY-SERIALS:

Key Serials: 0011 0013 0213 0229 0231 1279 1282 1581 2214 2481 2498 2585 3258 2740 3315

Multipunch Codes: 014 028 03- 04- 147 226 308 309 331 336 441 466 471 50& 53& 575 583
589 623 627 628 651 678 688 720 723

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C1984-059542

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> s de3240643/pn
L1          1 DE3240643/PN

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L1  ANSWER 1 OF 1  CAPLUS  COPYRIGHT 2003 ACS
AN  1984:618590  CAPLUS
DN  101:218590
TI  Conductive strip coatings and conductive perforation wall coatings on or
in circuit boards
IN  Tolls, Elmar; Schneider, Ehrenhard; Platzen, Rolf
PA  LPW-Chemie G.m.b.H., Fed. Rep. Ger.
SO  Ger. Offen., 8 pp.
CODEN: GWXXBX
DT  Patent
LA  German
IC  C25D007-00; C25D003-38
CC  72-8 (Electrochemistry)
Section cross-reference(s): 76
FAN.CNT 1
      PATENT NO.      KIND   DATE      APPLICATION NO.      DATE
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PI  DE 3240643       A1    19840530      DE 1982-3240643  19821104 <--
      DE 3240643       C2    19880107
PRAI DE 1982-3240643  19821104
AB  A well-known Cu electroplating bath for the prodn. of bright Cu
electroplates consists of Cu (as Cu2+) 10-50, H2SO4 20-220 g/L, and Cl-
1-200 mg/L and is used for the manuf. of conductive strip coatings and
conductive perforation wall coatings. The Cu electroplating bath addnl.
contains polyglycol or nonionic wetting agent and org. sulfo compds. with
groups rendering them water-sol., but is free of leveling agents. It is
used at a temp. of >30.degree. (preferably 40.degree.), and the c.d. is
maintained at 5-15 A/dm2. In an example, an epoxide conductive strip
reinforced with glass fibers is drilled and is electroplated in a bath of
the following compn.: Cu sulfate 80, H2SO4 200, polyglycol (av. mol. wt.
12,000) 2 g/L, Cl- 50, and N,N-diethyldithiocarbamic acid
(.omega.-sulfopropyl) ester Na salt 10 mg/L. At a temp. of 20.degree.,
for 20 min at a c.d. of 7.5 A/dm2, a layer thickness ratio of penetration
wall/surface of 0.75:1 was ascertained. If one carries out the
electroplating at 40.degree. under otherwise equal conditions, then a
layer thickness ratio of 0.92:1 is obtained.
ST  copper electroplating printed circuit; perforation wall coating circuit
board
IT  Polyoxyalkylenes
RL: USES (Uses)
      (in electroplating, of copper on conductive strips and perforation
      walls of circuit boards)
IT  Electric circuits
      (printed, boards, copper electroplating on)
IT  7440-50-8, uses and miscellaneous
RL: PEP (Physical, engineering or chemical process); PROC (Process)
      (electroplating of, on conductive strip and perforation walls of
      circuit boards)
IT  16887-00-6, uses and miscellaneous
RL: USES (Uses)
      (in copper electroplating on conductive strip and perforation walls of
      circuit boards)
IT  591-08-2D, reaction product with methylphenylthiourea and propane sulfone

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1120-71-4D, reaction product with acetylthiourea and methylphenylthiourea
4104-75-0D, reaction product with acetylthiourea and propane sultone
6142-42-3

RL: PRP (Properties)

(in electroplating, of copper on conductive strips and perforation
walls of circuit boards)

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